



IFW

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

RALF VAN BENTUM  
MANFRED HORSTMANN

Examiner: Lan Vinh

Group Art Unit: 1765

Serial No.: 10/624,712

Att'y Docket: 2000.106700/DE0122

Filed: July 22, 2003

Customer No.: 23720

For: TECHNIQUE FOR FORMING  
CONTACTS FOR BURIED DOPED  
REGIONS IN A SEMICONDUCTOR  
DEVICE

**RESPONSE TO OFFICE ACTION DATED AUGUST 26, 2005**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING 37 C.F.R. 1.8	
I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on the date below:	
October 24, 2005 Date	<i>Mary Paul</i> Signature

Sir:

This paper is submitted in response to the Office Action dated August 26, 2005, for which the three-month date for response is November 26, 2005.

No fees are believed to be due in connection with the present paper. However, should any fees be required under 37 C.F.R. §§ 1.16 to 1.21, the Director is authorized to deduct such fee from the Advanced Micro Devices, Inc. Deposit Account No. 01-0365/DE0122.<sup>1</sup>

Reconsideration of the application in view of the following remarks is respectfully requested.

<sup>1</sup> In the event the monies in that account are insufficient, the Director is authorized to withdraw funds from Williams, Morgan & Amerson, P.C. Deposit Account No. 50-0786/2000.106700.